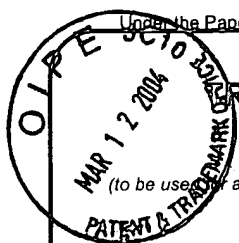


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**TRANSMITTAL
FORM**

(to be used for all correspondence after initial filing)

Application Number	10/616,294
Filing Date	July 9, 2003
First Named Inventor	Byung-Jin Choi
Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	P92/MII-44-26-03
Total Number of Pages in This Submission	

ENCLOSURES (Check all that apply)

<input type="checkbox"/> Fee Transmittal Form <input type="checkbox"/> Fee Attached <input type="checkbox"/> Amendment/Reply <input type="checkbox"/> After Final <input type="checkbox"/> Affidavits/declaration(s) <input type="checkbox"/> Extension of Time Request <input type="checkbox"/> Express Abandonment Request <input checked="" type="checkbox"/> Information Disclosure Statement <input type="checkbox"/> Certified Copy of Priority Document(s) <input type="checkbox"/> Response to Missing Parts/Incomplete Application <input type="checkbox"/> Response to Missing Parts under 37 CFR 1.52 or 1.53	<input type="checkbox"/> Drawing(s) <input type="checkbox"/> Licensing-related Papers <input type="checkbox"/> Petition <input type="checkbox"/> Petition to Convert to a Provisional Application <input type="checkbox"/> Power of Attorney, Revocation <input type="checkbox"/> Change of Correspondence Address <input type="checkbox"/> Terminal Disclaimer <input type="checkbox"/> Request for Refund <input type="checkbox"/> CD, Number of CD(s) _____	<input type="checkbox"/> After Allowance communication to Technology Center (TC) <input type="checkbox"/> Appeal Communication to Board of Appeals and Interferences <input type="checkbox"/> Appeal Communication to TC (Appeal Notice, Brief, Reply Brief) <input type="checkbox"/> Proprietary Information <input type="checkbox"/> Status Letter <input checked="" type="checkbox"/> Other Enclosure(s) (please identify below): Form 1449 - IDS Forty (40) References Return Receipt Postcard to Kenneth Brooks
Remarks 		

SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT

Firm or Individual name	Law Office of Kenneth C. Brooks
Signature	<i>Kenneth C. Brooks</i>
Date	3/2/04

CERTIFICATE OF TRANSMISSION/MAILING

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Typed or printed name	Alexis Sheffield		
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Choi et al. PATENT APPLICATION
Serial No.: 10/616,294 Group Art Unit: 1763
Filing Date: July 9, 2003 Examiner: Unassigned
For: SYSTEMS FOR MAGNIFICATION AND DISTORTION CORRECTION FOR
IMPRINT LITHOGRAPHY PROCESSES.

INFORMATION DISCLOSURE STATEMENT

Commissioner
for Patents
Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and a copy of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
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10/616,294	Choi et al.	07/09/2003

FOREIGN PATENT DOCUMENTS

<u>Document No.</u>	<u>Inventor</u>	<u>Pub. Date</u>
DE 2800476	Lamprecht et al.	07-13-1978
JP 1-196749	Matsumoto et al.	08-08-1989
WO 01/79592	Hallberg et al.	10-25-2001
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NON-PATENT DOCUMENTS

Chou et al. "Imprint of Sub-25 nm Vias and Trenches in Polymers," *Applied Physics Letters*, 67(21), pp. 3114-3116, 1995.

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Haisma, J. et al. "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," *Journal of Vacuum Science and Technology*, vol. 14, pp. 4124-4128, 1996.

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Chou, Stephen et al. "Lithographically-induced Self Assembly of Periodic Micropillar Arrays," *Journal of Vacuum Science and Technology*, vol. 17, pp. 3197-3202, 1999.

Ruchhoeft, P. et al. "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," *Journal of Vacuum Science and Technology*, vol. 17, pp. 2965-2982, 1999.

Choi, B.J. et al. "Design of Orientation Stages for Step and Flash Imprint Lithography," *Precision Engineering*, vol. 25, pp. 192-199, 2001.

Chou. "Nanoimprint Lithography and Lithographically Induced Self-Assembly," *MRS Bulletin*, pp. 512-517, July 2001.

CERTIFICATE OF MAILING

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Signed: Alexis Sheffield
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 Date: March 2, 2004

Respectfully,



Kenneth C. Brooks
 Reg. No. 38,393

P.O. Box 81536
 Austin, Texas 78708-1536
 Telephone: 512-527-0104
 Facsimile: 512-527-0107
patentsrus@earthlink.net

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4

Application Number

10/616,294

Filing Date

07/09/2003

First Named Inventor

Choi et al.

Group Art Unit

1763

Examiner Name

Unassigned

Attorney Docket Number

P92/MII-44-26-03

U.S. PATENT DOCUMENTS

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Application Number	10/616,294
Filing Date	07/09/2003
First Named Inventor	Choi et al.
Group Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	P92/MII-44-26-03

Sheet	2	of	4
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		Application Number	10/616,294
		Filing Date	07/09/2003
		First Named Inventor	Choi et al.
		Group Art Unit	1763
		Examiner Name	Unassigned
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OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	A27	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	A28	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	A29	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
	A30	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	A31	FELDMAN et al., "Wafer chuck for manification correction in x-ray lithography," American Vacuum Society, 1998, pp. 3476-3479.	
	A32	SCHEER et al., "Problems of the Nanoimprinting Technique for Nanometer Scale Pattern Definition," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3917-3921, vol. B 16(6).	
	A33	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	
	A34	CHOU et al., "Lithographically-Induced Self Assembly of Periodic Polymer Micropillar Arrays," Journal of Vacuum Science and Technology, Nov/Dec 1999, pp. 3197-3202, vol. B 17(6).	
	A35	RUCHHOEFT et al., "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," Journal of Vacuum Science and Technology, 1999, pp. 2965-2982, vol. 17.	
	A36	CHOI et al., "Design of Orientation Stages for Step and Flash Imprint Lithography," Precision Engineering, Journal of the International Societies for Precision Engineering and Nanotechnology, 2001, pp. 192-199, vol. 25.	
	A37	CHOU, "Nanoimprint Lithography and Lithographically Induced Self-Assembly," MRS Bulletin, July 2001, pp. 512-517.	

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